



Leibniz ScienceCampus GraFOx
(Growth and fundamentals of oxides for electronic applications)

1st Annual Meeting
20 July 2017, Berlin-Adlershof

Thursday, July 20, 2017

R. 0'119, Erwin-Schrödinger-Zentrum, Rudower Chaussee 26, 12489 Berlin.

09:00	<i>Welcome Coffee</i>
09:30-09:45	Welcome and introduction Henning Riechert <i>Paul-Drude-Institut für Festkörperelektronik, Berlin, Germany</i>
09:45-11:00	Symposium talks (I) Band Structure Engineering and Defect Control of Oxides for Energy Applications Su-Huai Wei <i>Beijing Computational Science Research Center Beijing, Beijing, China</i> Thin-Film Alchemy: Engineering Oxide Films to Unleash their Hidden Properties Darrell Schlom <i>Cornell University, New York, USA</i>
11:00-11:30	<i>Coffee break</i>

11:30-12:45	<p>Symposium talks (II)</p> <p>Chemical and electronic interface processes at In₂O₃ based semiconductor gas sensor surfaces and metal/oxide junctions Marcel Himmerlich <i>Technische Universität Ilmenau, Ilmenau, Germany</i></p> <p>Toward Realization of Ga₂O₃ for RF and Power Electronics Applications Gregg Jessen <i>Air Force Research Laboratory, Dayton, Ohio, USA</i></p>
<i>12:45-14:00</i>	<i>Lunch</i>
14:00-16:00	<p>Cluster reports</p> <p><i>14:00-14:30</i> C1 – Physical properties <i>14:30-15:00</i> C2 – Surfaces <i>15:00-15:30</i> C3 – Growth <i>15:30-16:00</i> C4 - Atomic defects, doping, and defect engineering</p>
<i>16:00-16:30</i>	<i>Coffee Break</i>
16:30-18:00	PhD Poster session